



FORM PTO-1449 INFORMATION DISCLOSURE STATEMENT	ATTY DOCKET NO. 51256	SERIAL NO. 10/726,052
	APPLICANT(S): Shelnut et al.	
	FILING DATE: 12/02/2003	ART UNIT: 2874

UNITED STATES PATENT DOCUMENTS

EXAM. INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLASS	FIL. DATE IF APPR
PH	AA	5,200,487	04/06/1993	Lagarde et al.		—	
↑	AB	5,378,585	01/03/1995	H. Watanabe		—	
	AC	5,554,465	09/10/1996	H. Watanabe		—	
	AD	5,612,170	03/18/1997	Takemura et al.		—	
	AE	5,672,672	09/30/1997	Amano et al.		—	
	AF	6,054,253	04/25/2000	Fardad et al.		—	
	AG	6,087,064	07/11/2000	Lin et al.		—	
	AH	6,088,492	07/11/2000	Kaneko et al.		—	
	AI	6,144,795	11/07/2000	Dawes et al.		—	
↓	AJ	6,344,305	02/05/2002	Lin et al.		—	
PH	AK	6,731,857	05/04/2004	Shelnut et al.		—	

FOREIGN PATENT DOCUMENTS

		DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUB CLASS	TRAN YES/NO
PH	BA	WO 98/26315	06/18/1998	International		—	
↓	BB	0 543 761 A1	05/26/1993	Europe		—	
	BC	8-304644	11/22/1996	Japan		—	Yes
	BD	8-259895	10/08/1996	Japan		—	Yes
↓	BE	6-172533	06/21/1994	Japan		—	Yes
PH	BF	6-256523	09/13/1994	Japan		—	Yes

Examiner:

Pham T. H. Palmer

Date: 06/04/2005

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PH	BG	31 33039	11/24/2000	Japan			Yes
	BH	10-253845	09/25/1998	Japan			Yes
	BI	10-148729	06/02/1998	Japan			Yes
	BJ	8-327842	12/13/1996	Japan			Yes
	BK	06-172533	06/21/1994	Japan			Abstract
	BL	57-168246	10/16/1982	Japan			Abstract
	BM	58-096654	06/08/1983	Japan			Abstract
	BN	63-279245	11/16/1988	Japan			Abstract
	BO	04-271306	09/28/1992	Japan			Abstract
	BP	04-366958	12/18/1992	Japan			Abstract
PH	BQ	2003-3048984A	02/21/2003	Japan			Abstract

OTHER DOCUMENTS (INCLUDING AUTHOR, TITLE, DATE, PERTINENT PAGES, ETC.)

PH	CA	Bagley et al., "The Processing and Use of Organosilicon Polymers for Photonic Applications"; Polymer Engineering and Science, Mid-September 1989, Vol. 29, No. 17, pp. 1197-1199.
PH	CB	Brault et al., "Bilevel Polysiloxane Resist for Ion-Beam and Electron-Beam Lithography"; SPIE Vol. 539 Advances in Resist Technology and Processing II (1985); pp. 70-73.

Examiner: Phan T.H. Palmer

Date: 10/16/2005